

Supporting Information

An innovative GC-MS, NMR and ESR combined, gas-phase investigation during chemical vapor deposition of silicon oxynitrides films from tris(dimethylsilyl)amine

*Laura Decosterd, Konstantina C. Topka, Babacar Diallo, Diane Samelor, Hugues Vergnes, François Senocq, Brigitte Caussat, Constantin Vahlas, Marie-Joëlle Menu**

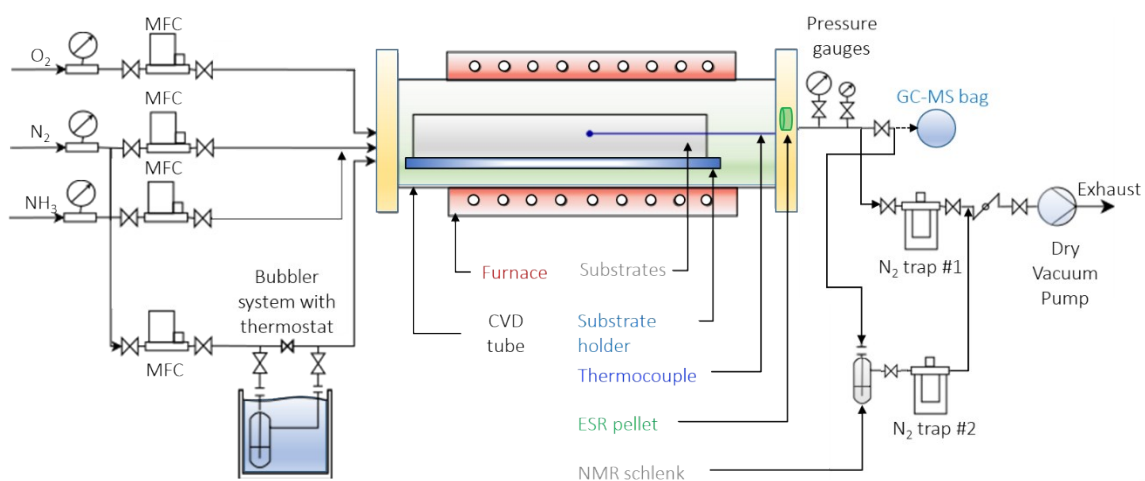


Figure S1. Schematic representation of the tubular CVD reactor

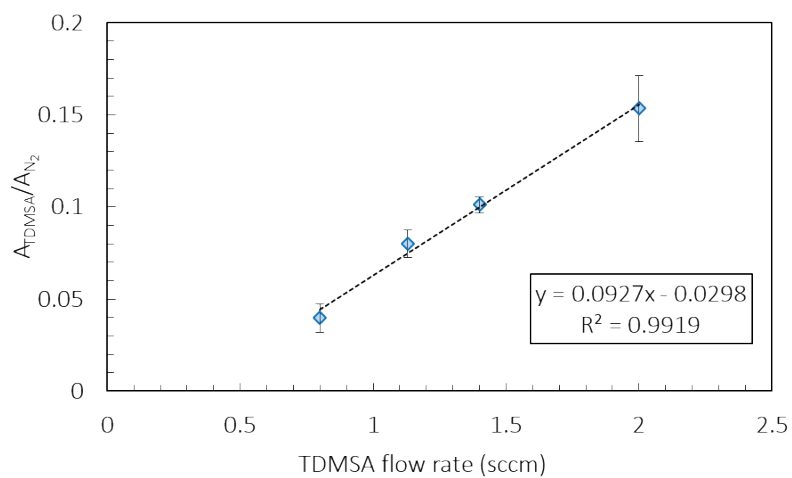


Figure S2. Calibration curve of TDMSA